

# ***CCD and CMOS Imaging Devices for Large (Ground Based) Telescopes***

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BNL

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# “Large Telescopes”

Survey telescope

Deep probe

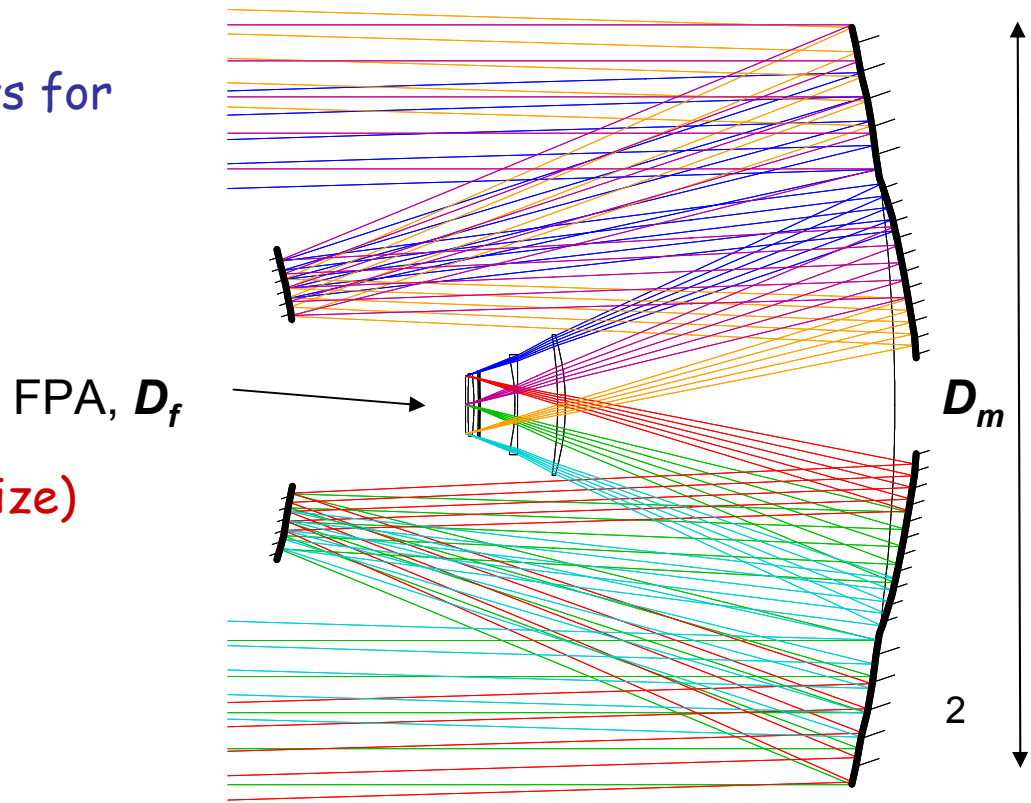
• Primary Mirror $dia.=D_m$ , Area= $A$	<b>Large (~8m)</b>	<b>Very large (~30m)</b>
• $f$ -number $f/\#$	$\sim 1/1.2$	$\sim 1/30-40$
• Focal Plane Array $dia.=D_f$	<b>Large (~60cm)</b>	<b>Medium (~20cm)</b>
• Field of View $\Omega \propto D_f/D_m$	$\sim 3-4$ degrees	$\sim 20$ arc min
• Etendue $A\Omega$	$\sim 330m^2deg^2$	
• Plate Scale arcsec/ $\mu m$	<b>0.2</b>	

Science Drivers: Wide area surveys for dark energy studies

FPA Requirements:

- Increase Area
- Increase QE in near IR
- Reduce PSF (diffusion and pixel size)
- Increase readout speed

e.g., Pan STARRS, LSST



# Growth of mosaics

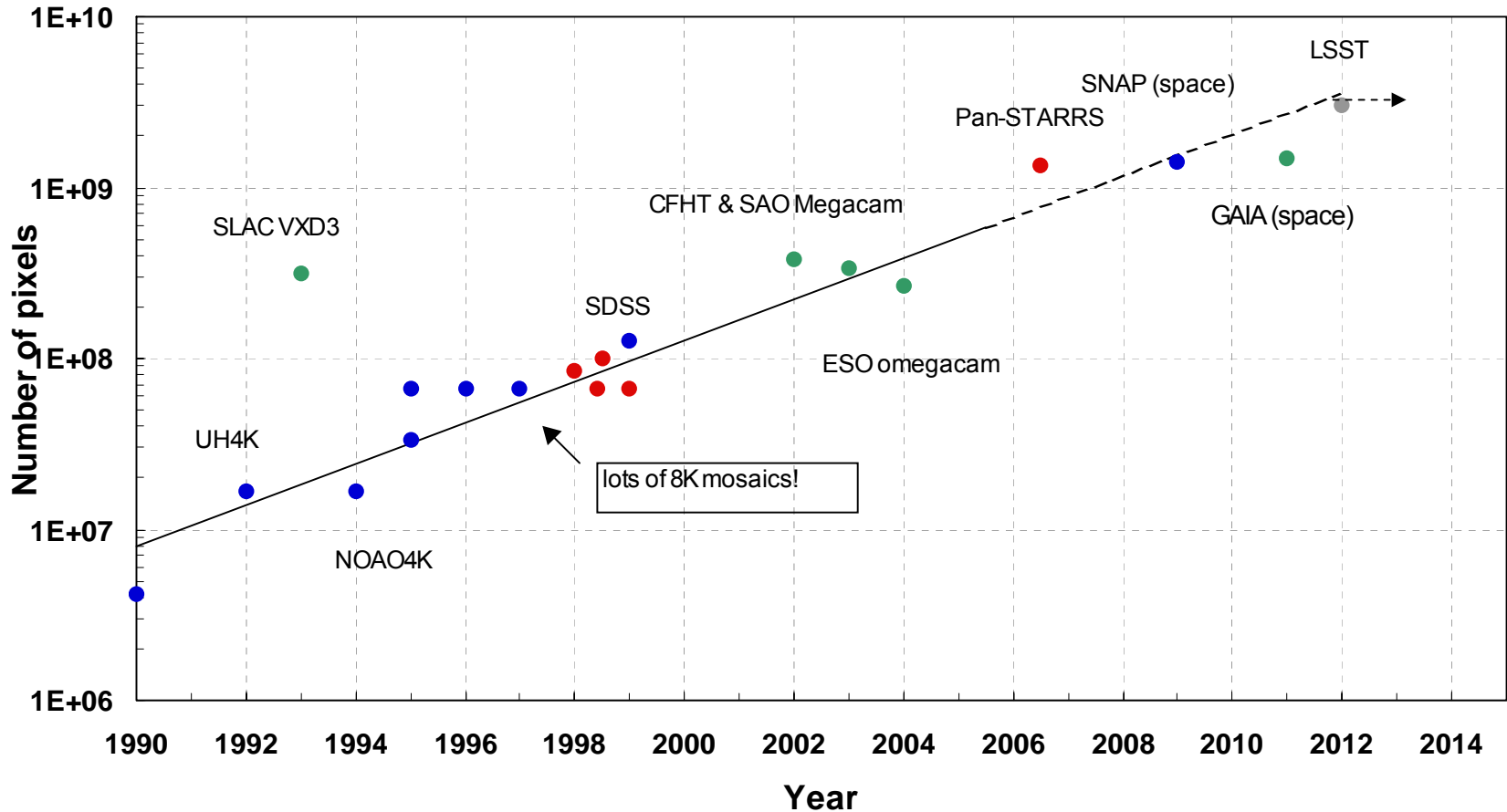


Illustration of focal plane sizes, from Luppino/Burke 'Moore's' law

Focal plane size doubles every 2.5 years

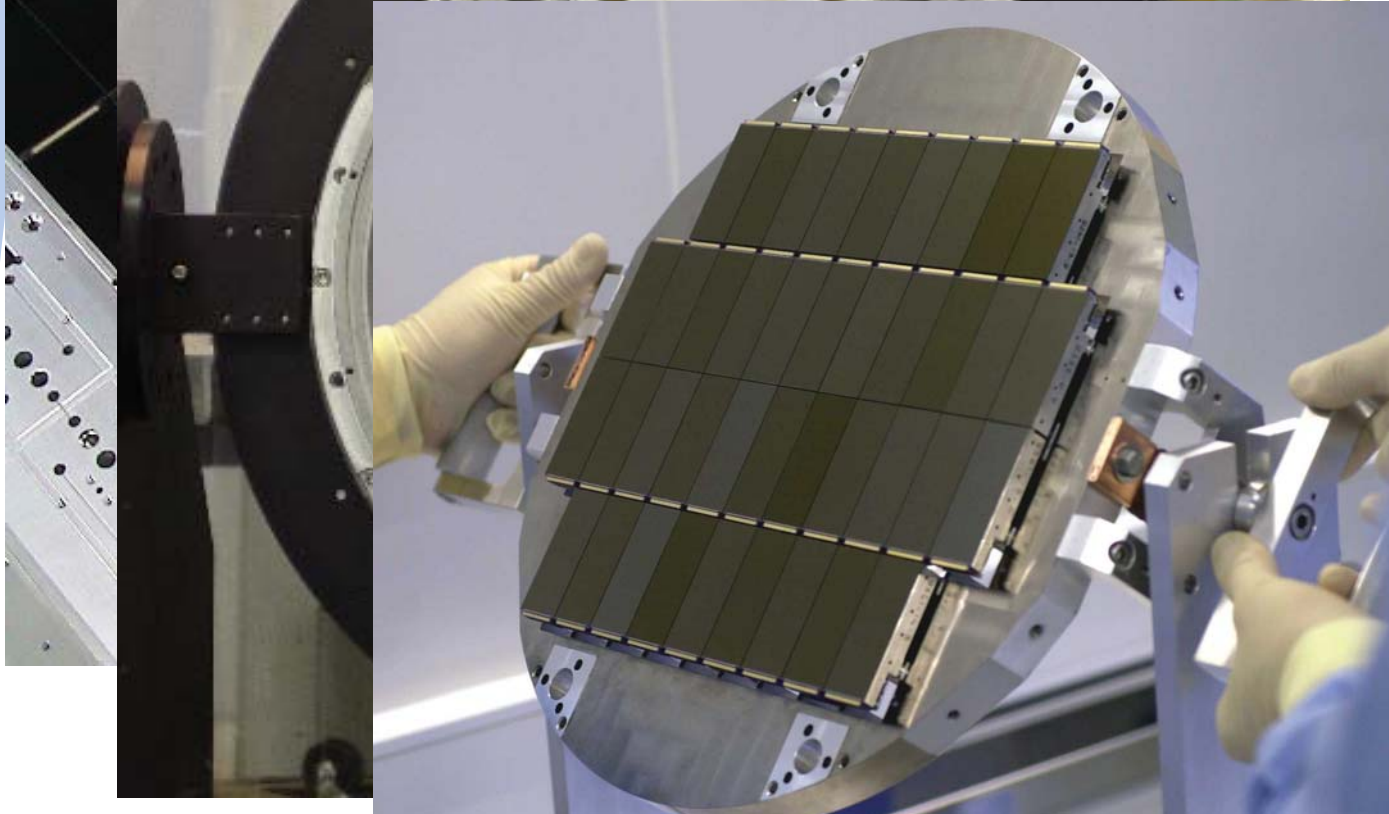
# Ground-based mosaics-3



ESO VST Omegacam



SAO MMT Megacam



CFHT Megacam  
Operational- April 2003

# SAO MMT Megacam



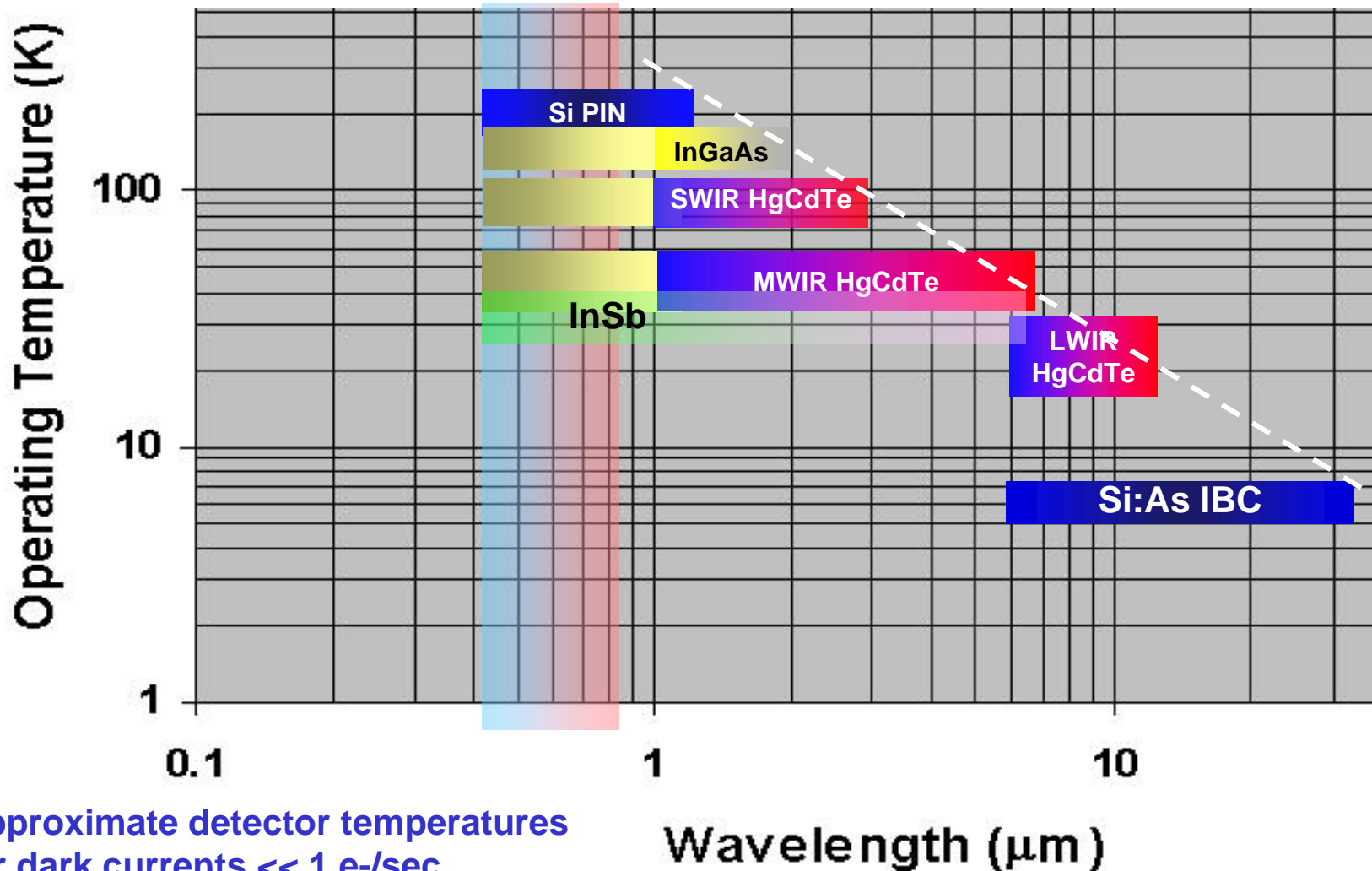
**4x9**

**E2v CCD42-90**

**2048x4608 13.5  
micron pixels**

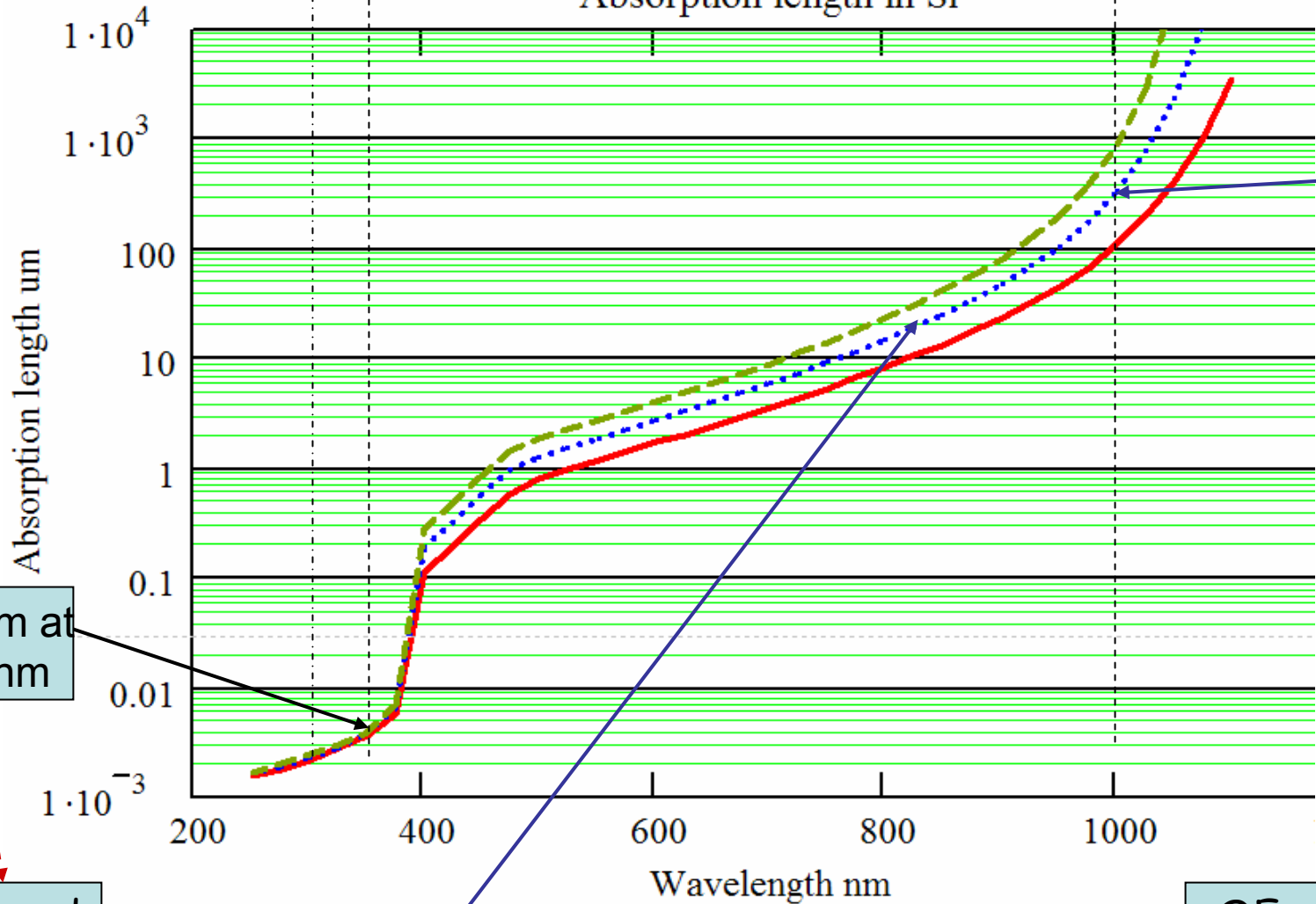
**200kHz**

# Temperature and Wavelengths of High Performance Detector Materials



From: Loose, Hoffman, Suntharalingam, SDW, Taormina 2005

Absorption length in Si



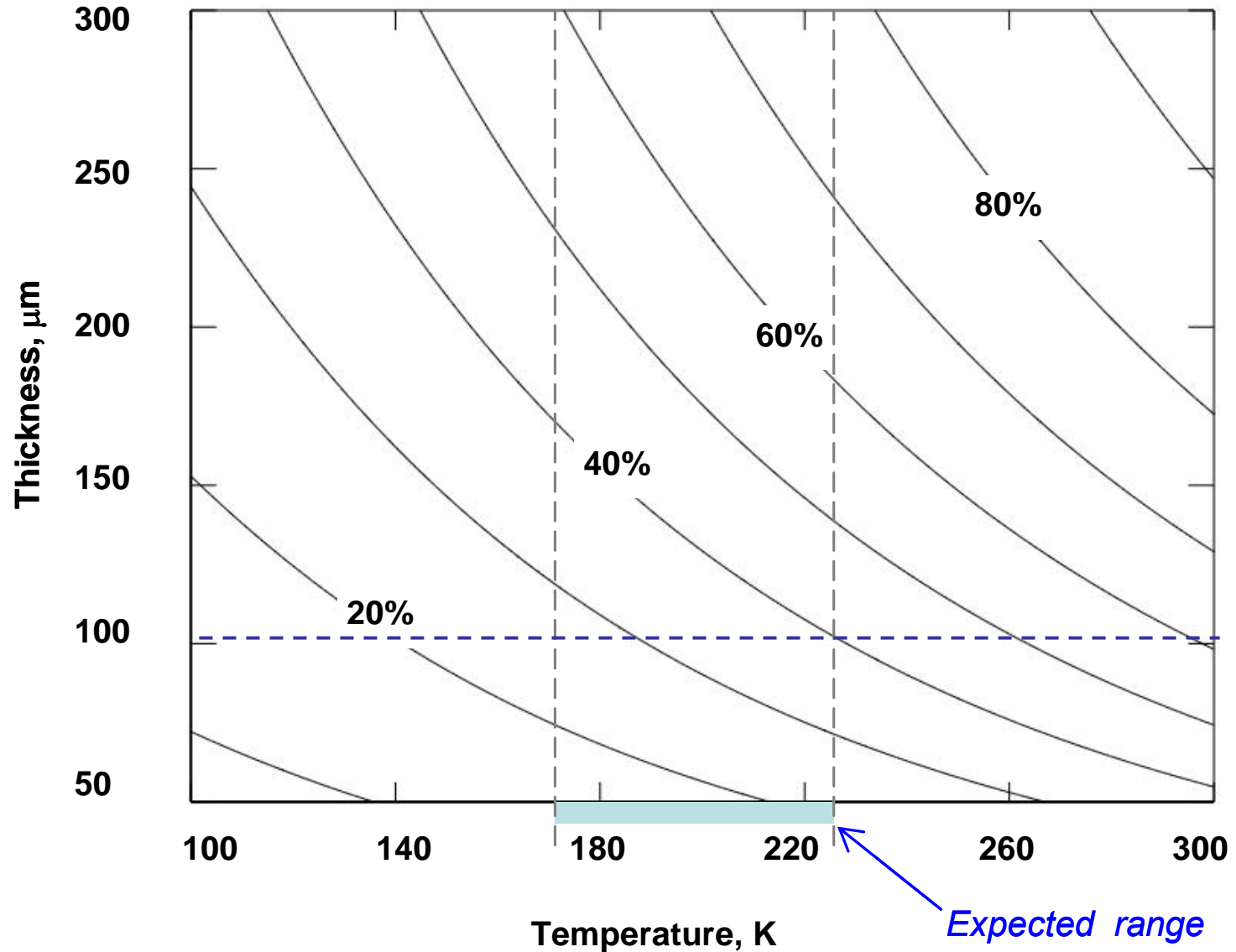
~4nm at 350nm

QE and Window problem

~300μm at 173K

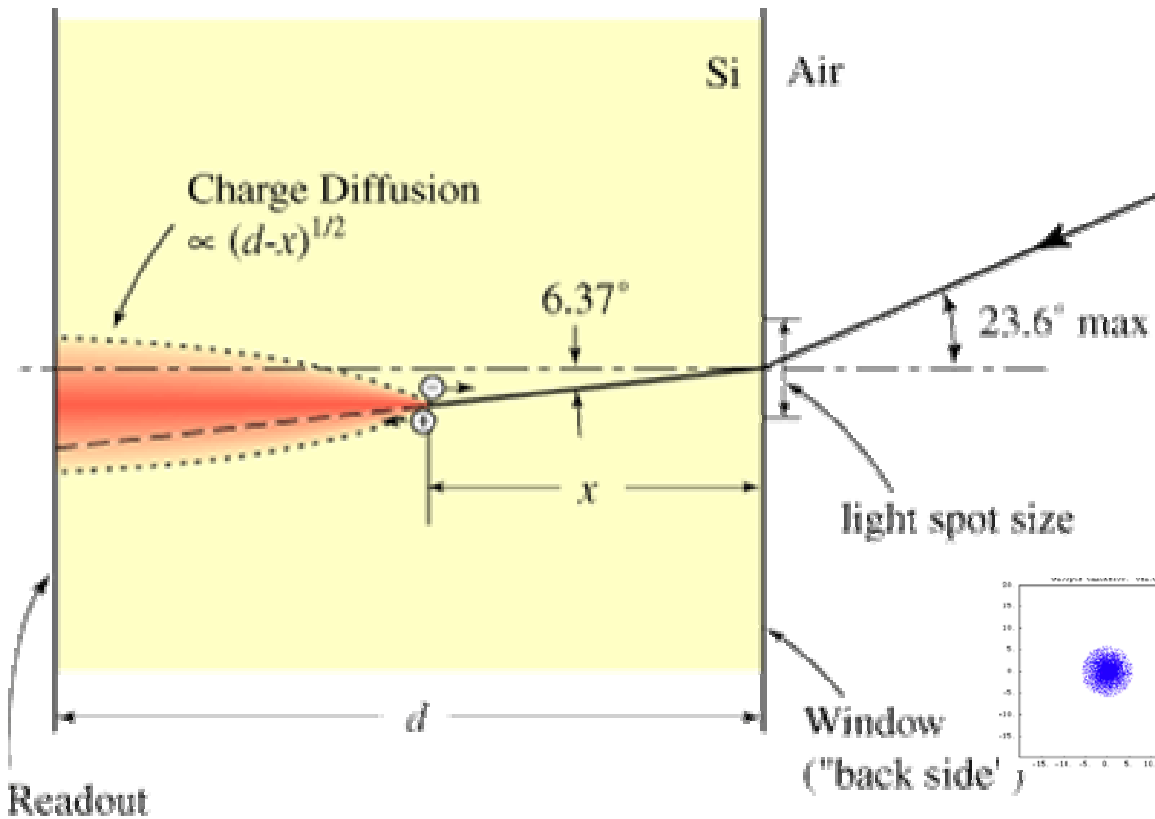
QE and PSF problem

# Internal QE vs temperature and silicon thickness, for 1000nm wavelength.



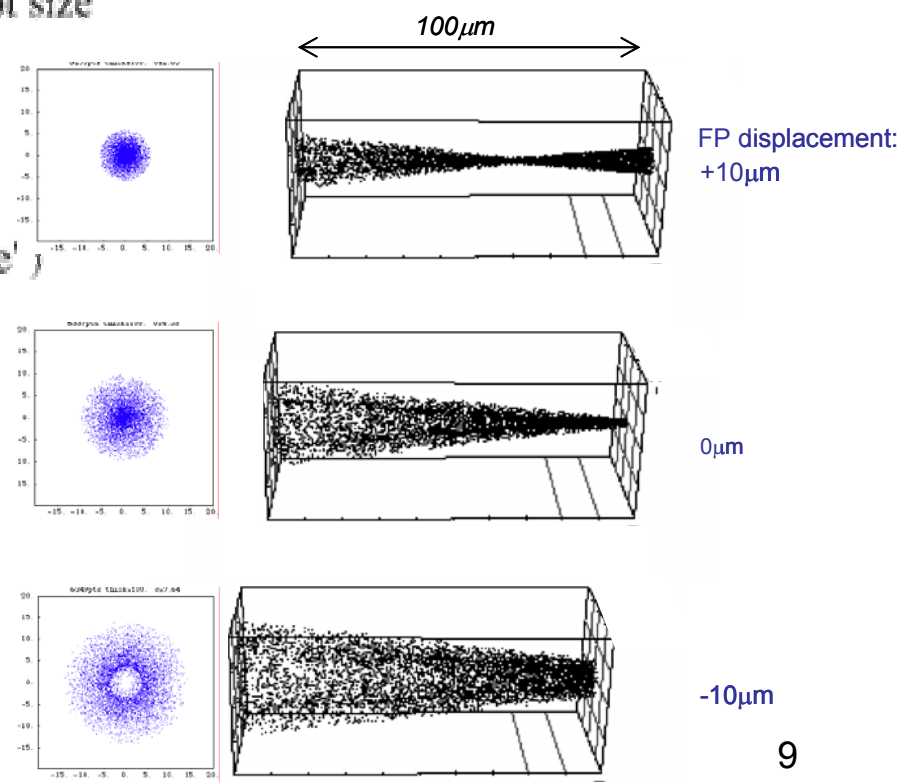


# Point Spread Function (PSF) in Si



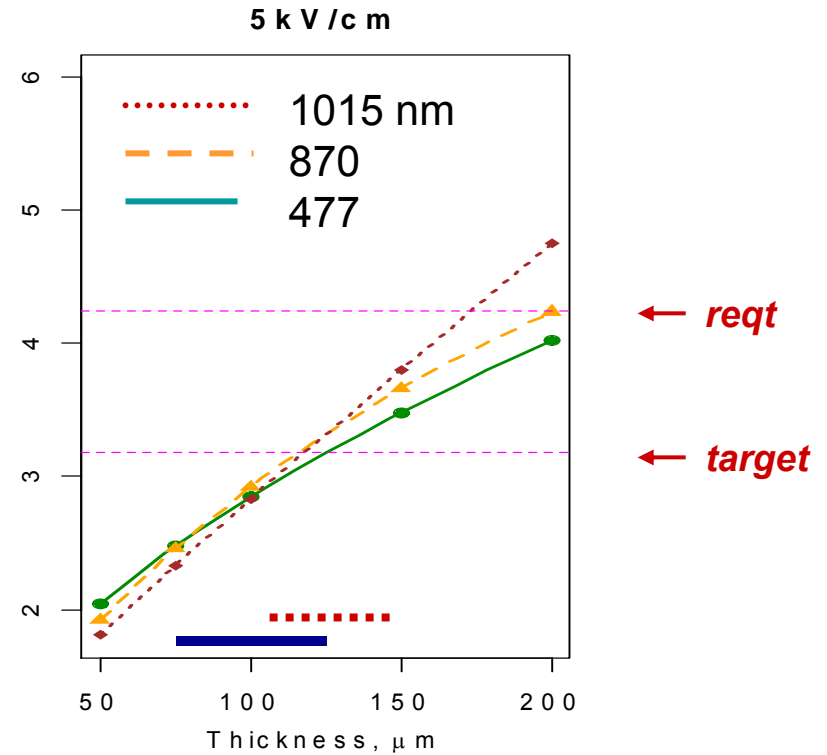
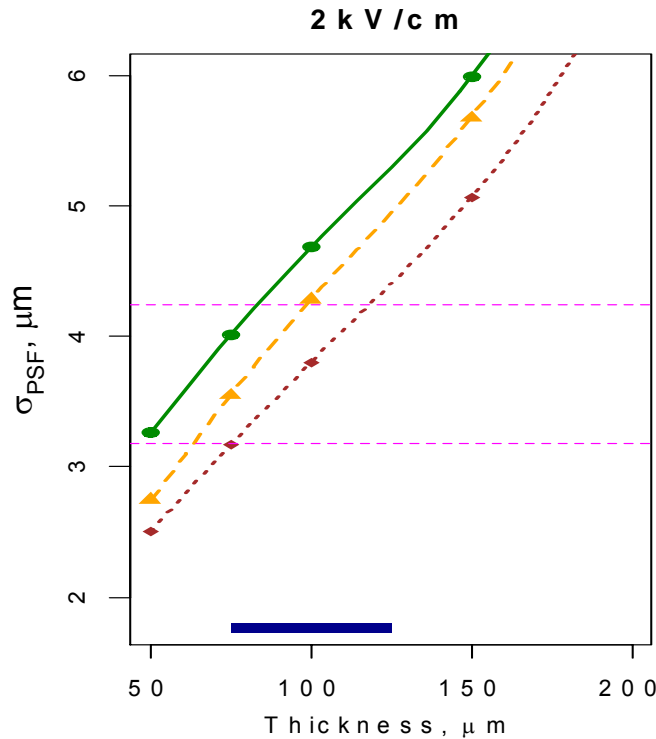
*LSST (f~1.2!)*

Simulation by P. Takacs, BNL:

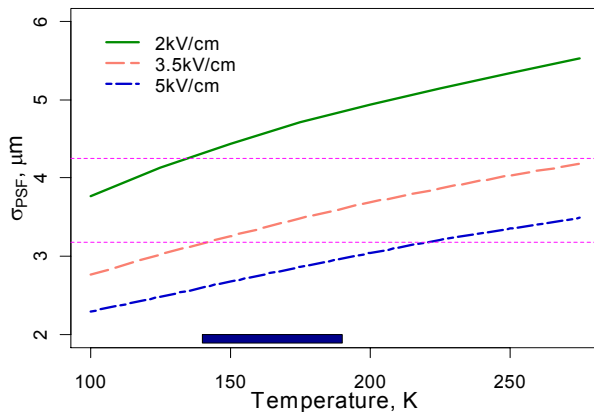


*Light spot, cone, absorption  $\rightarrow$  ionization, charge diffusion  $\rightarrow$  PSF*

# Monochromatic PSF *rms* vs. thickness and electric field



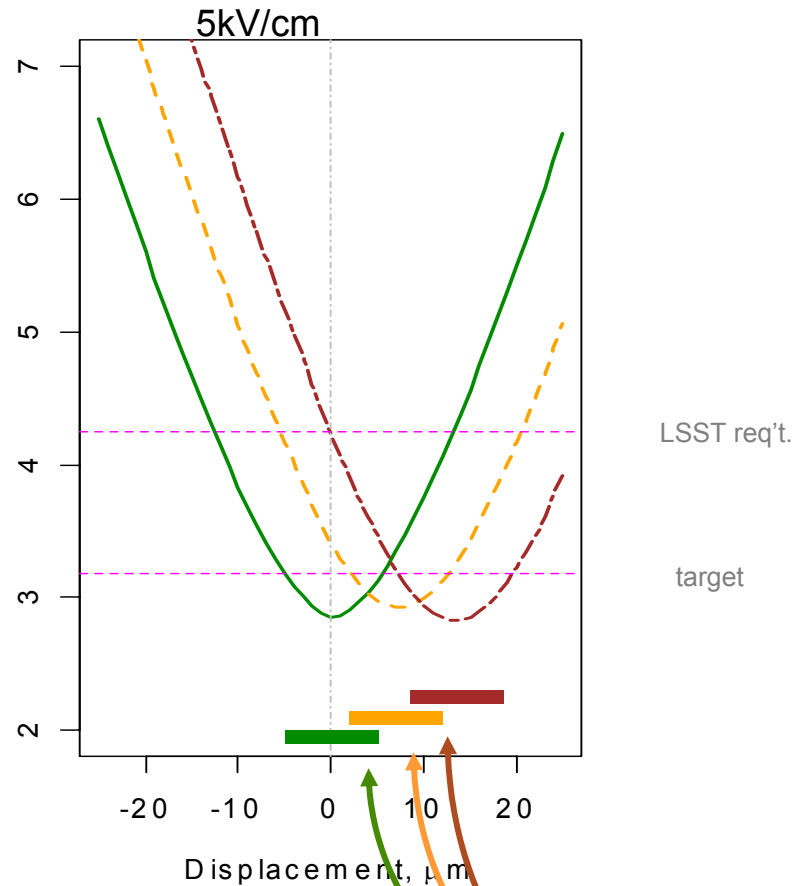
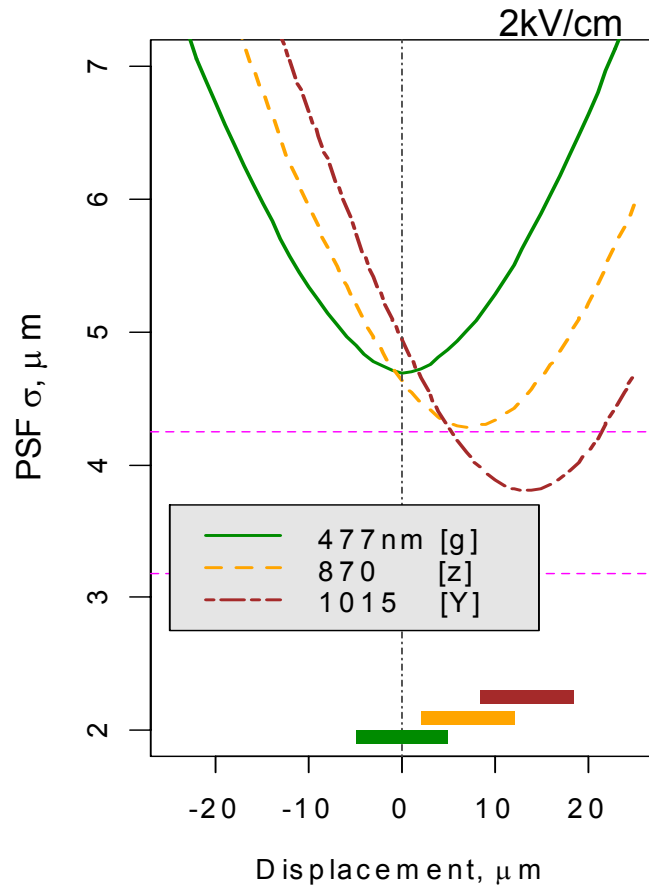
## PSF vs T and E for electrons



- Includes effects of *diffusion and divergence*.
- *Velocity saturation effects included*
- *Focal plane position adjusted at each thickness and wavelength for minimum overall PSF.*

*resistivity 10 k $\Omega$ -cm, p-type, overdepleted*

# Optimal focal plane position varies with wavelength due to divergence of f/1.2 beam



*resistivity 10 k $\Omega$ -cm, p-type, 100  $\mu\text{m}$*

Allowed focal plane non-flatness

# Partial vs Full Depletion

- Conventional CCDs 15-20  $\mu\text{m}$  thick on 20-100 ohmcm silicon cannot be fully depleted with 15-20 volts.

*PSF (rms) ~ thickness of undepleted region ( $\geq \sim 6-7 \mu\text{m}$ )*

- Full depletion essential for minimal charge spreading, *PSF (rms)  $< \sim 4 \mu\text{m}$*

- Methods to ensure full depletion:

- *High-resistivity substrate*  $>5 \text{ kohm cm}$
- *Bias on p+ (n+) back-surface* (30-50 volts on 100  $\mu\text{m}$ )

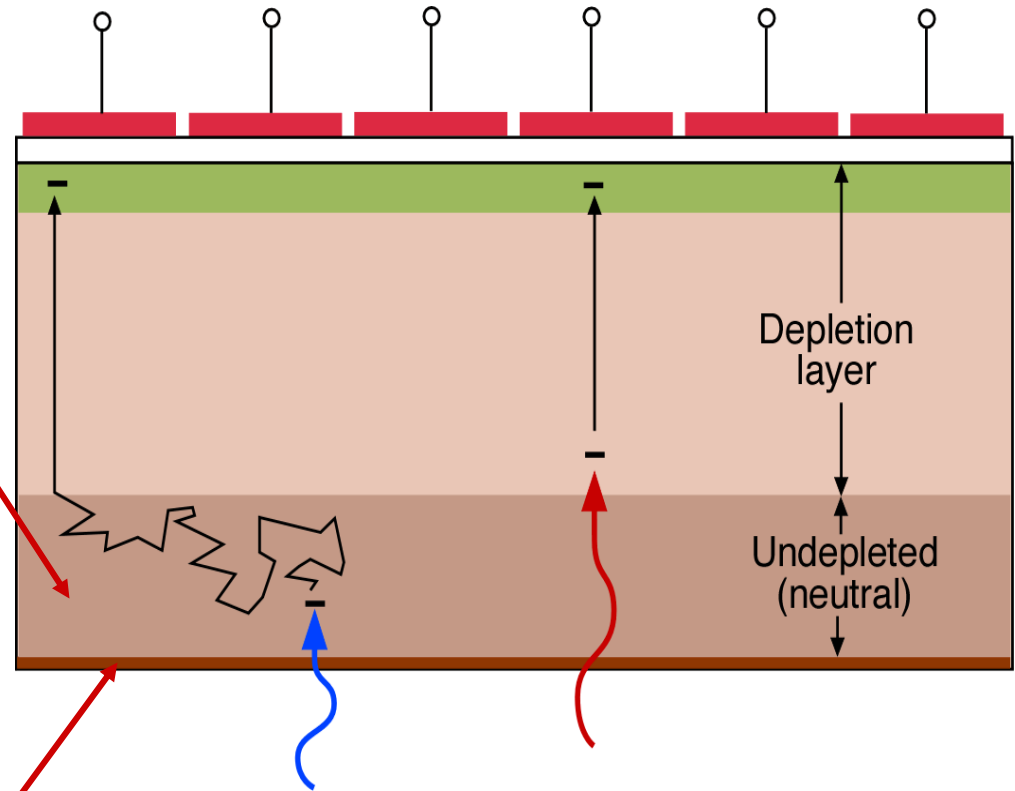
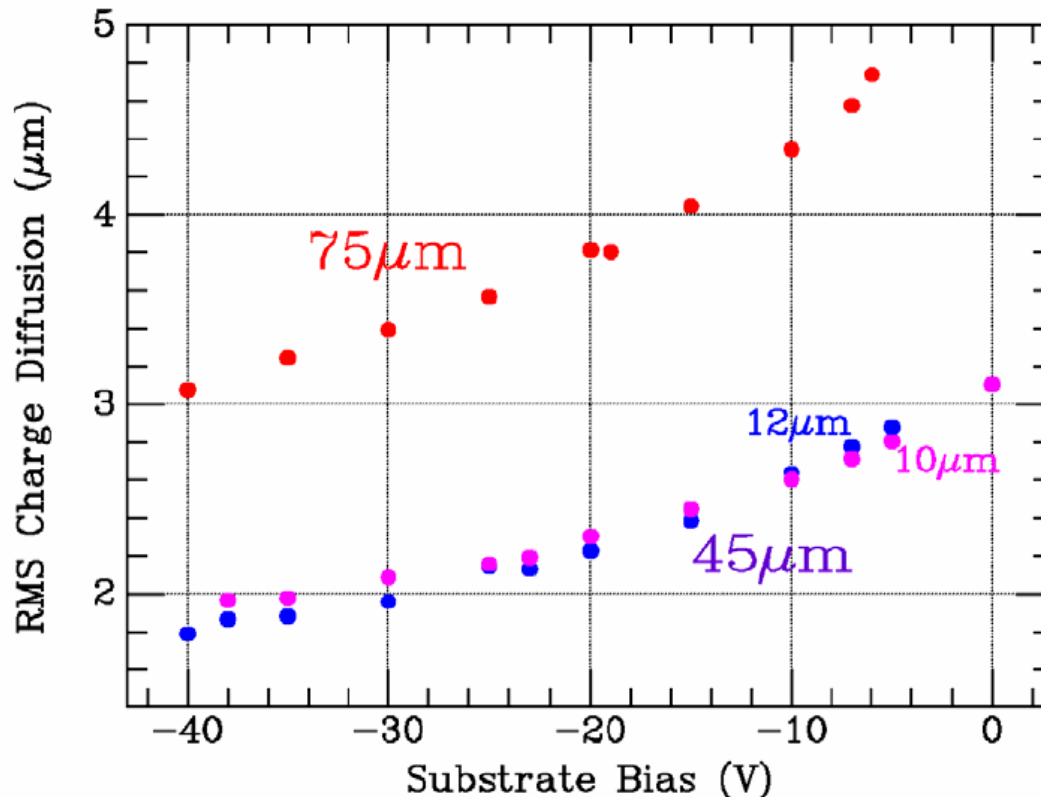


Illustration from:  
Barry Burke

# *Can the predicted small diffusion be achieved?*

CCDs developed at LL for PanSTARRS.  
B. Burke, J. Tonry, et al. results:



Calculation incl. velocity saturation effects predicts  $\sim 2.5 \mu\text{m rms}$  at 40 volts for electrons (p-substrate).

For LBNL/SNAP CCD results see S.Holland, this conference

# Window Technology

*A highly doped layer at the window required to terminate the field and leave a thin conductive layer at the surface.*

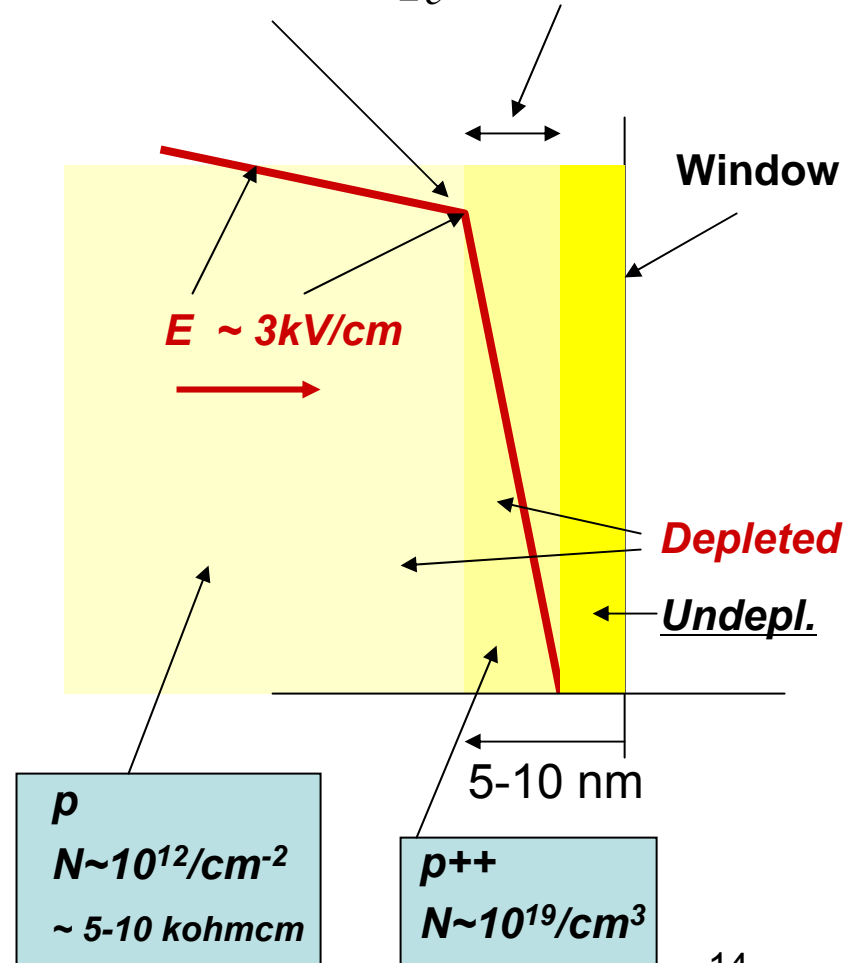
*Highly doped layer thickness  $\ll \sim 10$  nm to allow uv light into the sensitive (depleted) region.*

*Technologies under development (must be compatible with antireflective coating):*

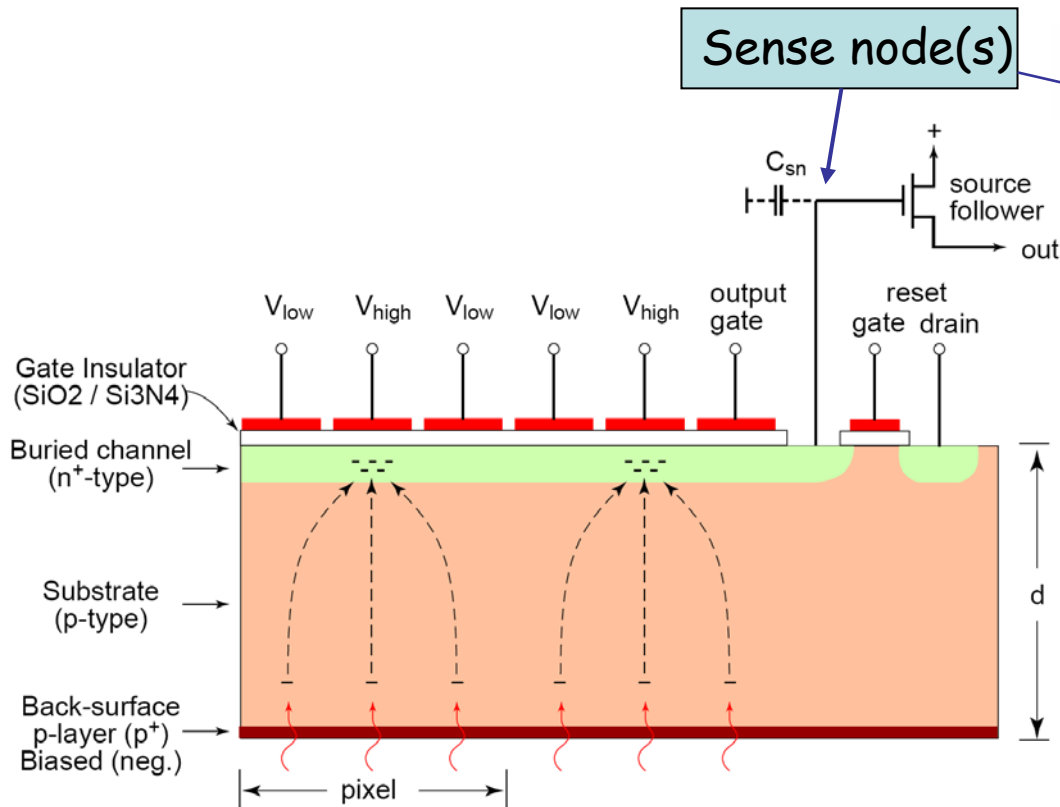
- *Ion implantation followed by laser annealing - low T process (LL)*
- *Doped polysilicon deposition - high T process (LBNL), presentation by S. Holland*
- *Chemisorption charging - very good for uv response, but no conductive layer (ITL)*

“Ohmic contact”:

$$\epsilon E = q_e N \Delta x$$

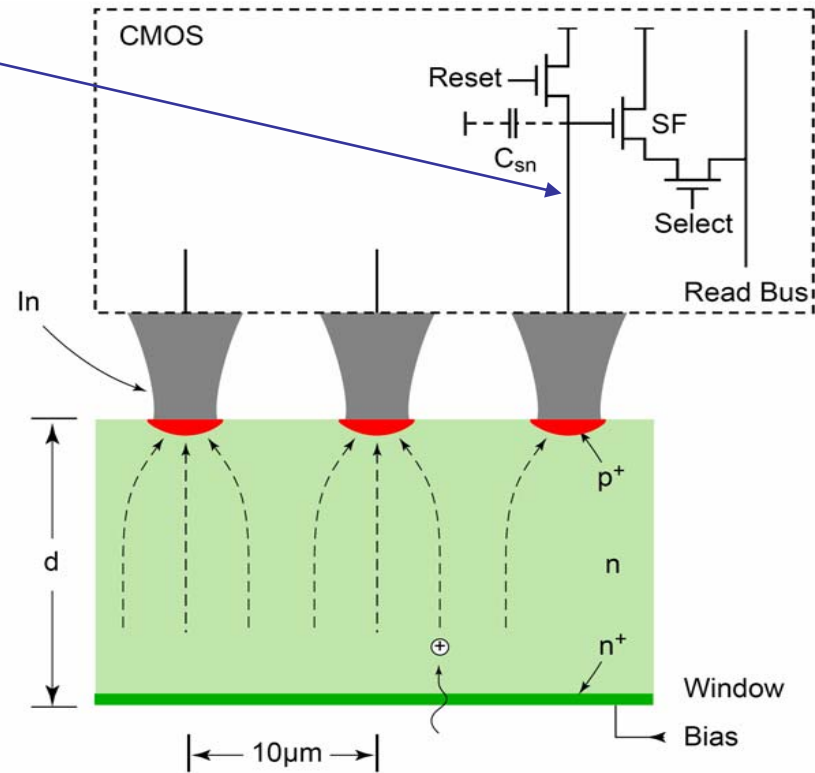


## CCD



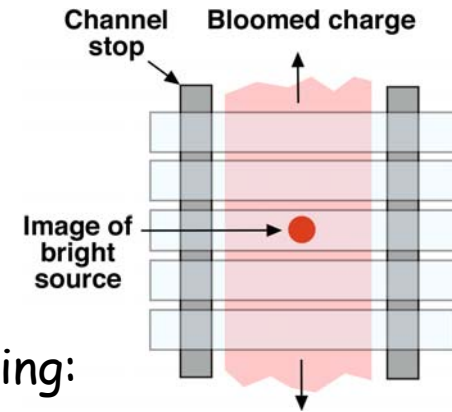
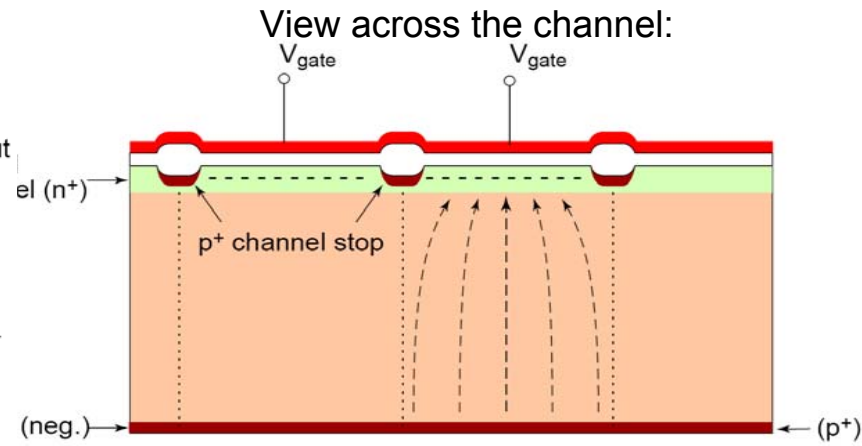
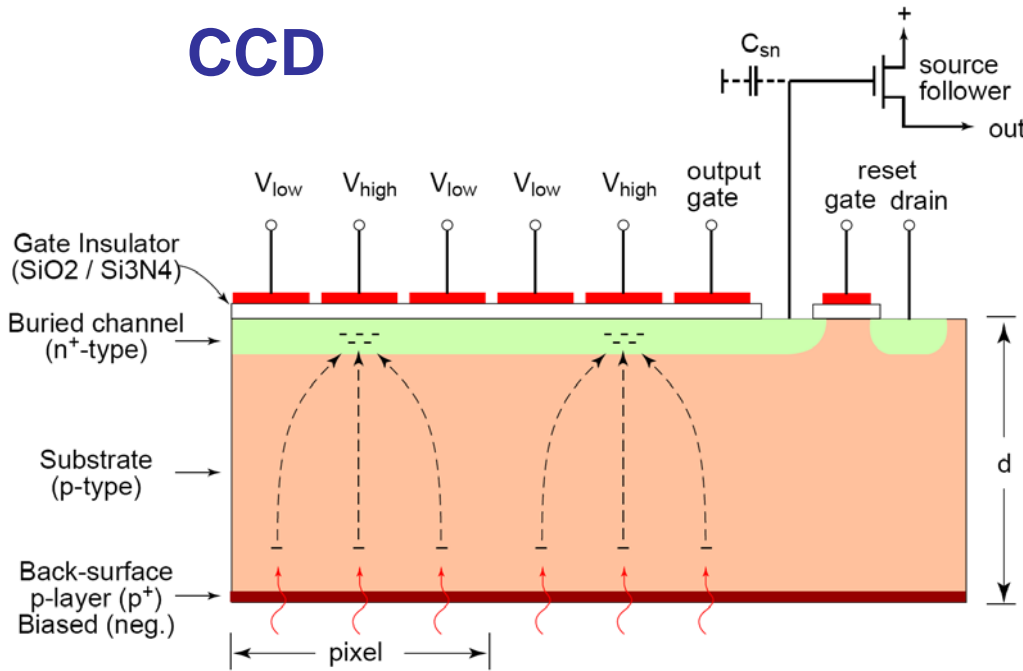
- In a CCD, the signal charge is transferred **serially** by a noiseless process (very high CTE) to **a single sense node**, where it is converted to a signal voltage.
- Pixels are read out **after** the integration is completed.

## Hybrid PIN-CMOS



- In a PIN CMOS sensor, the charge to voltage conversion takes place **in parallel at the sense node of each pixel**.
- The signal voltage can be read out “up the ramp” **during** integration.

# CCD



- Photoresponse non-uniformity <1%
- Dark current in inversion mode ~0.001 e<sup>-</sup>/pixel sec
- Correlated double sampling each clock cycle
- More complex clock amplitude and phasing requirements
- High power dissipation with segmented readout
- Independent window biasing → design constraints

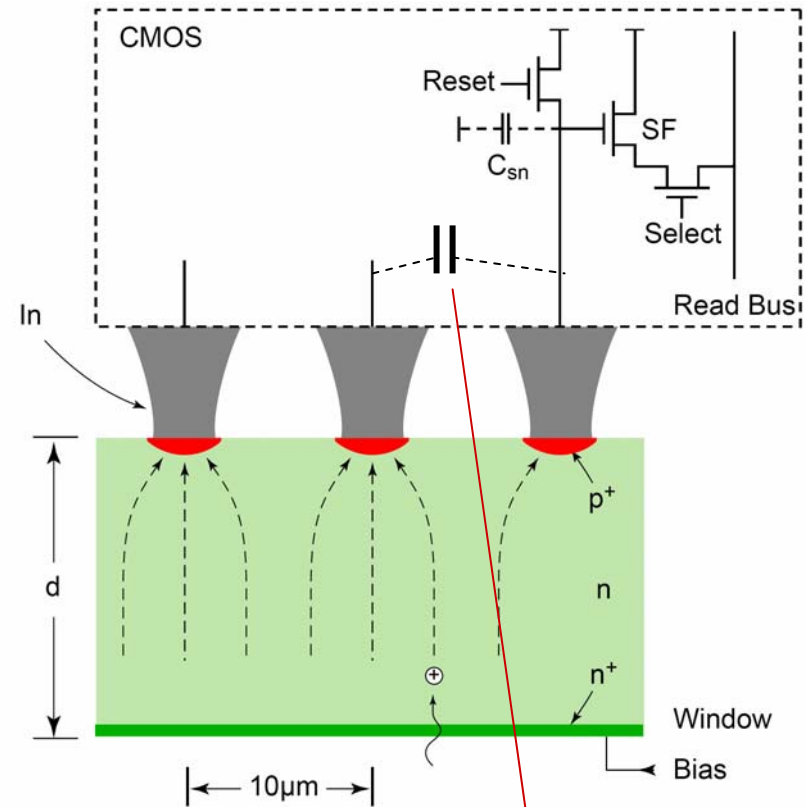
• Blooming:



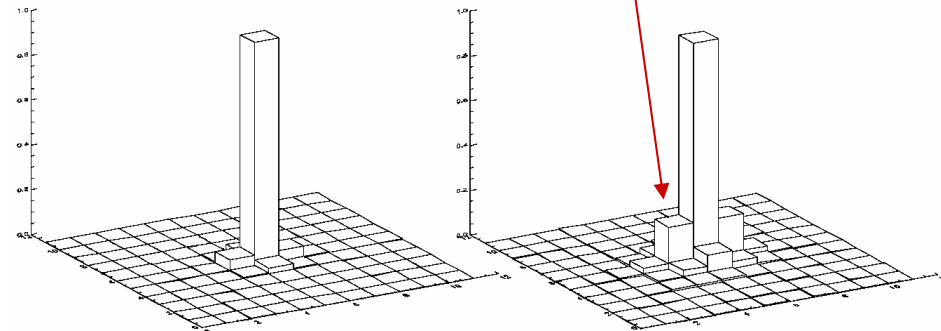


# PIN-CMOS

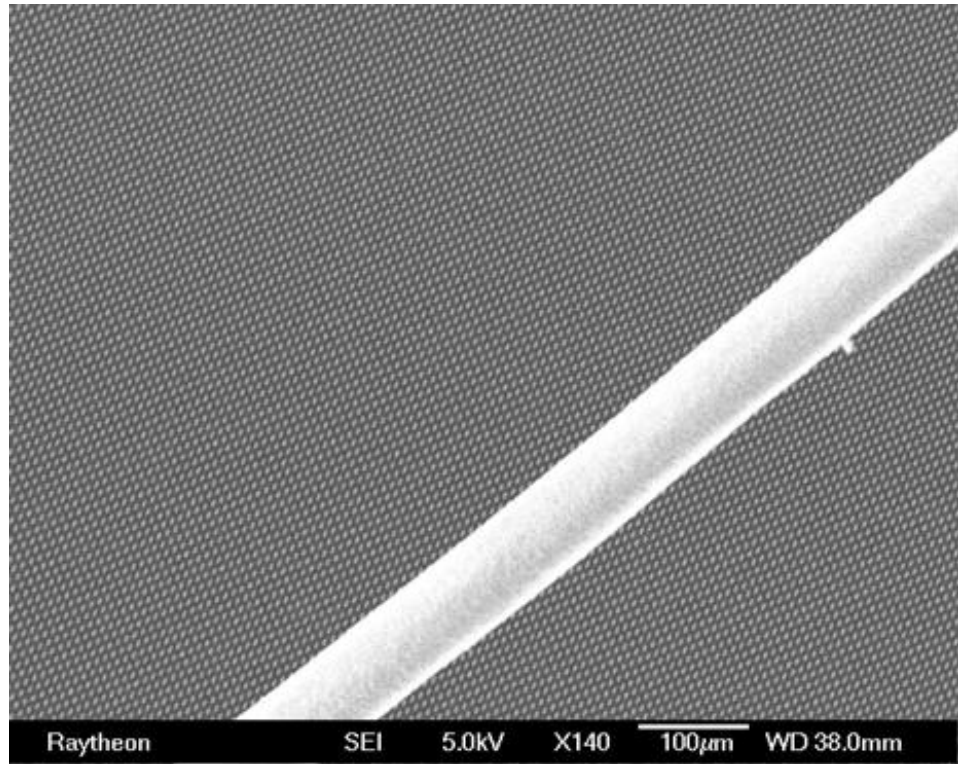
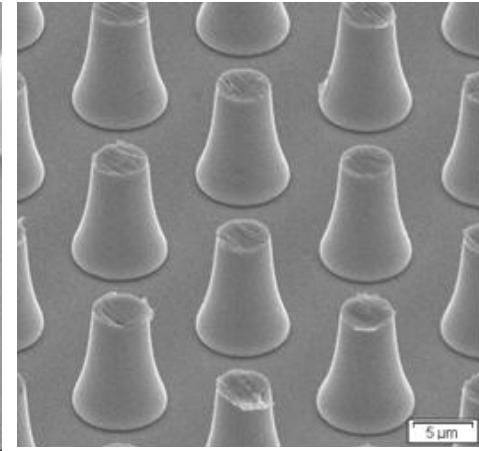
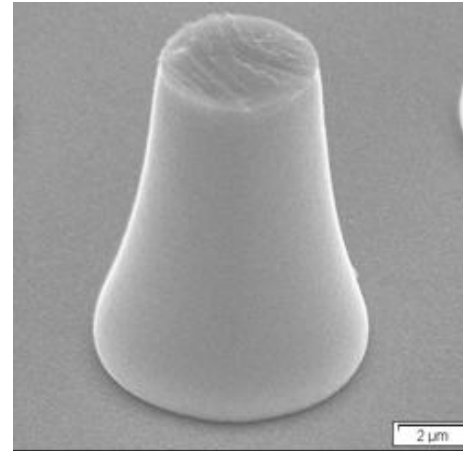
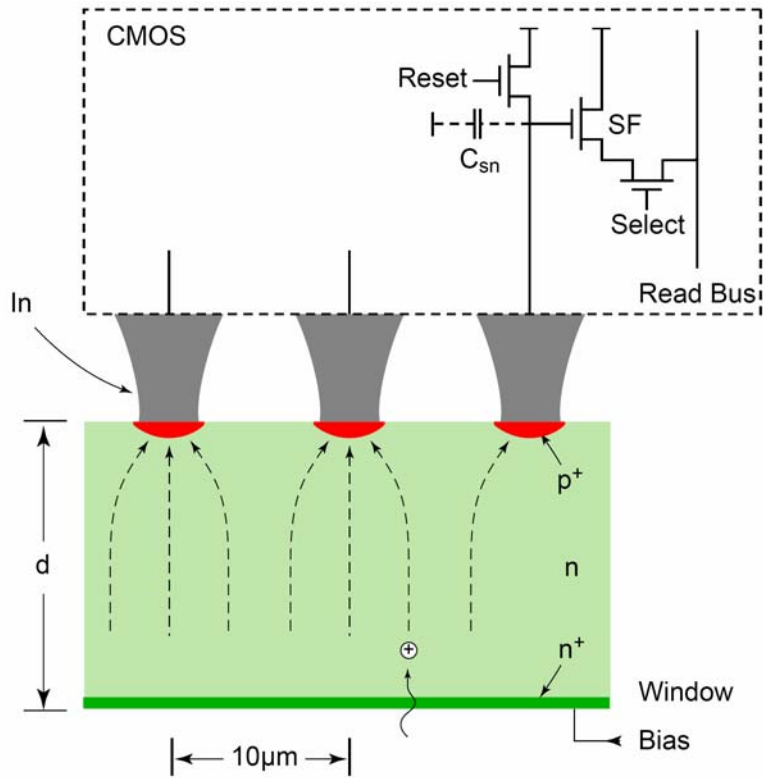
- Independent optimization of the PIN and CMOS design and processing
- Electronic shutter by reset transistors
- Blooming control
- Large dynamic range by readout "up the ramp"; addressable guider readout
- Lower power dissipation, low voltage for CMOS
- Fixed pattern noise
- pixel-to-pixel (stable) gain differences due to amplifier per pixel
- capacitive (deterministic) crosstalk to adjacent pixels
- CDS over longer time intervals



J. Beletic. Et al.:



# Indium Bump Bonding

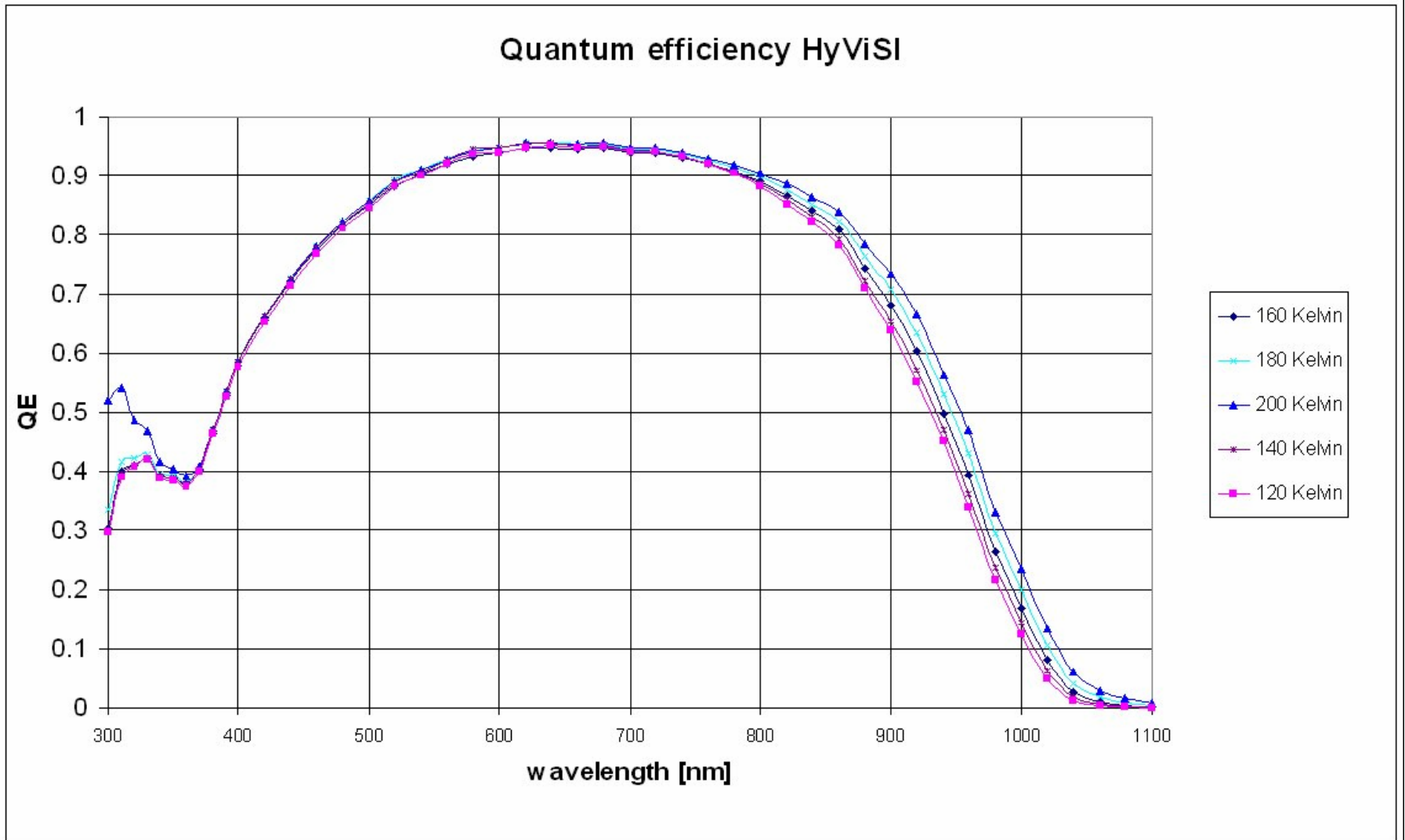


Bond yield by RVS and RSC  
>0.999

Indium interconnect array on 8 μm centers  
compared to a human hair. →

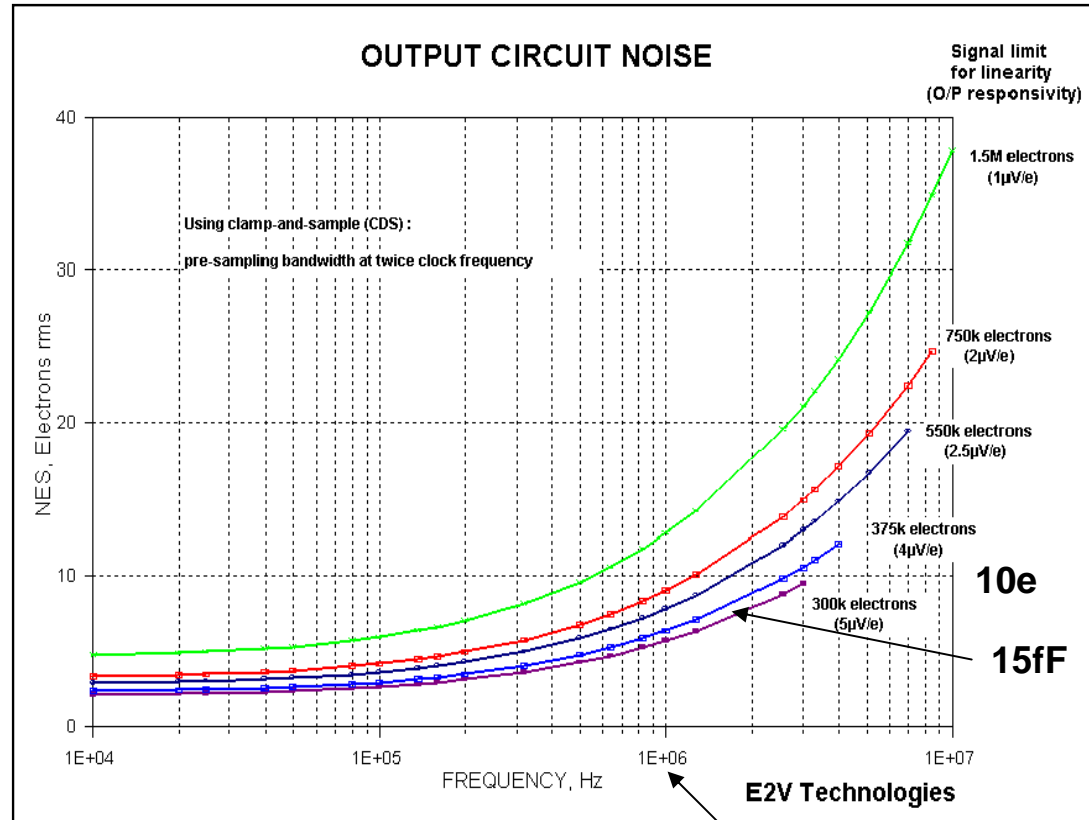
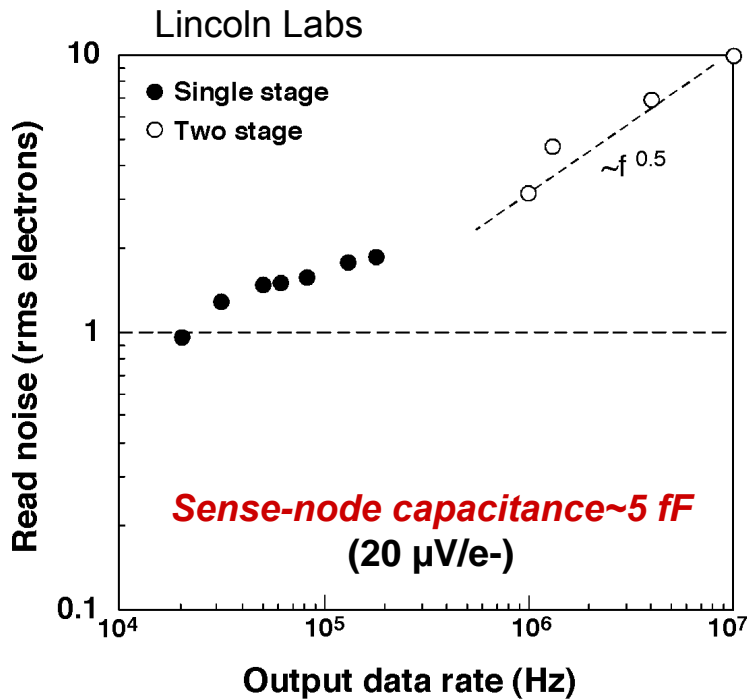
From: K.T. Veeder et al., "Enabling Technologies  
for Large Hybrid Focal Plane Arrays with Small  
Pixels", Raytheon Vision Systems

RSC - H2RG (2Kx2K, 18  $\mu\text{m}$  pixel) HyViSI Measured quantum efficiency (courtesy Reinhold Dorn, ESO).



This HyViSI array has a detector layer that is 75 microns thick and a single layer anti-reflection coating of SiO<sub>2</sub> that is 1200Å thick.

# Readout Noise in CCDs



Source Follower transistor:

Channel length L:

Channel width W:

Power:

By CCD process:

~4-6 μm

~45 μm

**5-10 mW**

MOS(P):

~0.4-0.5 μm

~10 μm

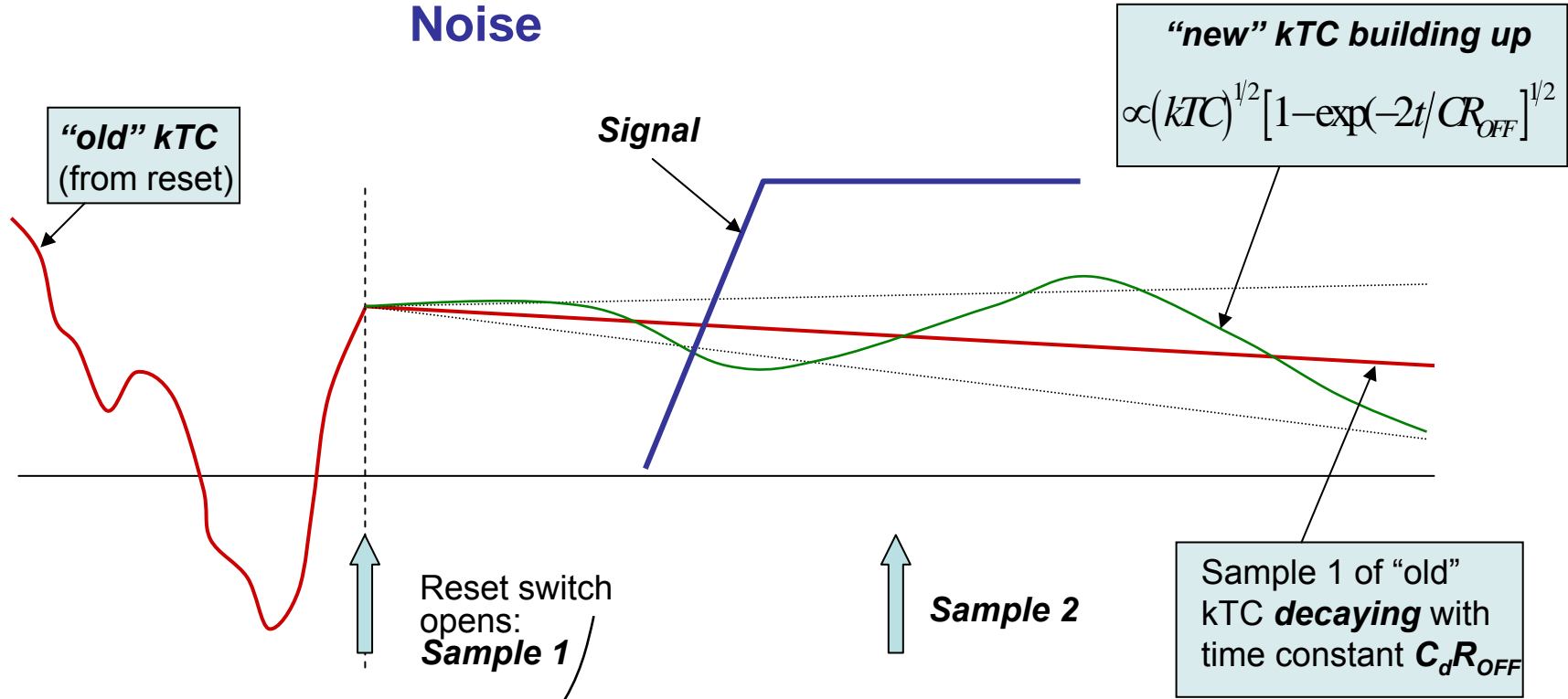
**<100 μW**

1 MHz

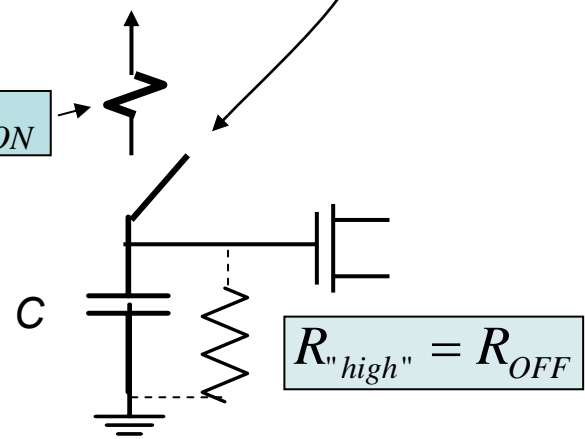


*For equal noise!*

# Correlated Double Sampling (CDS) and $kTC$ Noise



**Active Pixel (or CCD)**



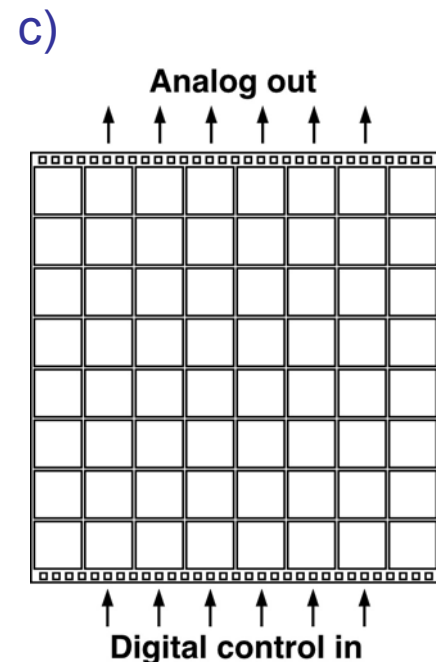
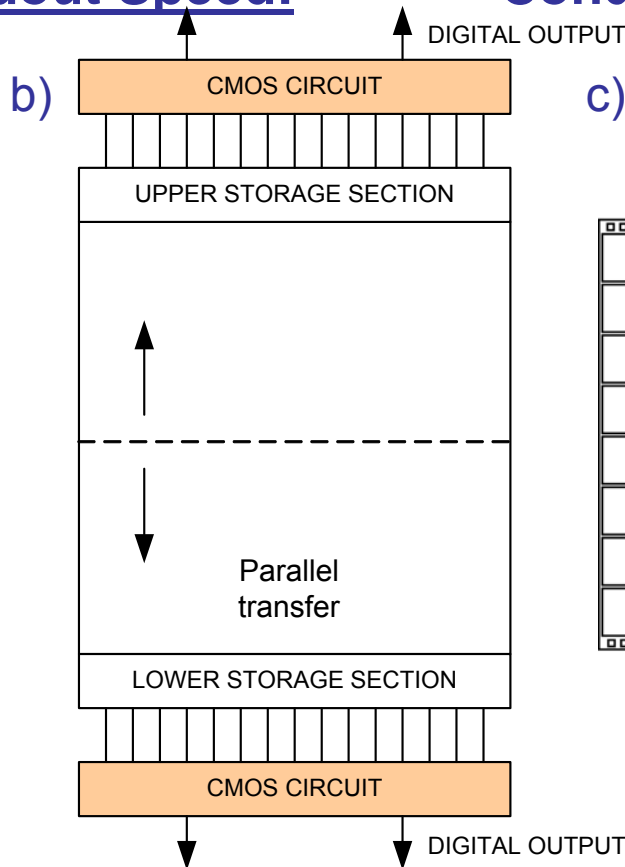
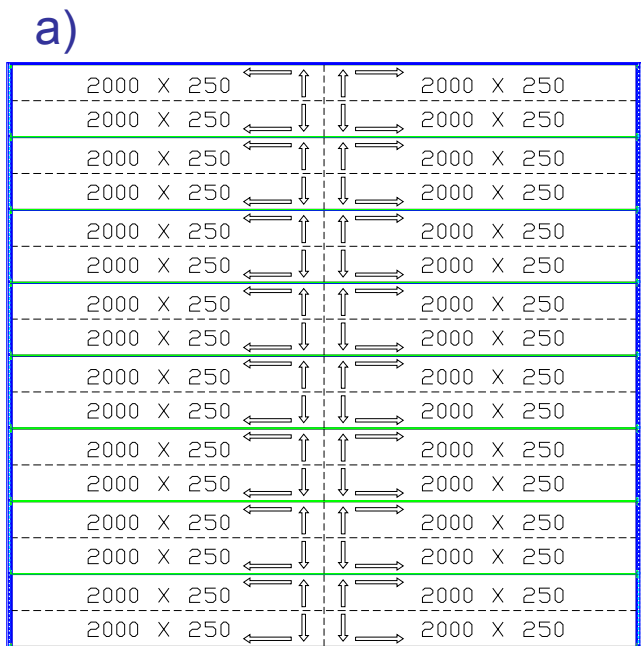
$$R_{OFF} / r_{ON} \approx 10^6 - 10^{11}$$

Example:

- $C \sim 20 \text{ fF} \rightarrow kTC \sim 40 \text{ e rms!}$
- $r_{ON} \sim 10^3 \text{ ohms} \quad r_{ON} C \sim 20 \text{ ps}$
- $R_{OFF} \sim 10^{13} \text{ ohms} \quad R_{OFF} C = 0.2 \text{ s}$

# Segmenting CCDs for Readout Speed:

Condition:  $< 5 \text{ e rms}$



All arrays  $4k \times 4k = 16 \text{ Mpixels}$

**Segments:** Up to 32

**Advantages:** Short columns -  
-blooming localized

**Disadvantages:** Non-contiguous  
imaging due to serial registers

**Application:** LSST-like telescopes

**Source followers:** on CCD

Up to  $2 \times 4k!$

High frame rate

Long columns  
(blooming)

X-ray detectors

On or off CCD

64 (or more)

Combination of a) and b) if  
not an OTA

Density of outputs too low  
for direct bump bonding to  
CMOS readout

On CCD (Pan STARRS), or off

## *Trends:*

- CCDs ~75-200  $\mu\text{m}$  thick for astronomy (more for x-rays) -  
-being developed by several manufacturers.
- Conventional CCD readout will be limited to a small number  
of segments (power dissipation, number of connections).
- Silicon PIN CMOS remain to be proven and accepted in  
astronomy. If so, will prevail for short readout times. CCDs  
will still be best for long integration times.
- Pixel size will bottom out (full well charge, readout time, ...).
- CCD-CMOS hybrids need to be explored for high  
performance imaging in astronomy (they are being actively  
developed for other fields).